JC17 Rec'd PCT/PTO 06 JUN 2005

PCT/KR2002/002316 IPEA/KR 28.01.2005

REAR PLATE FOR PLASMA DISPLAY PANEL

Technical Field

The present invention relates to a rear plate of a plasma display panel.

Background Art

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As generally known in the art, a plasma display panel (PDP) is a display device having a front glass substrate and a rear glass substrate between which a discharge space is formed, so that plasma discharge may generate in the discharge space, thereby causing phosphors in the discharge space to be excited and emit light, so as to display a screen. In comparison with liquid crystal panel, the PDP can display an image at a higher speed and can easily realize a larger screen. Therefore, PDPs are employed in a field of a television with a higher quality and a larger screen.

Hereinafter, an AC PDP, which is currently the mainstream of PDPs, will be described.

A PDP includes a front plate and a rear plate assembled in parallel with each other. The front plate includes a front glass substrate, a plurality of discharge sustaining electrodes formed on a lower surface of the front glass substrate, bus electrodes formed on lower surfaces of the discharge sustaining electrodes, a dielectric layer covering the discharge sustaining electrodes and the bus electrodes, and a protection layer formed on a lower surface of the

AMENDED SHEETS

Further, the rear plate includes a dielectric layer. rear glass substrate, address electrodes formed on an upper surface of the rear glass substrate, a dielectric of the address surfaces on upper laver formed electrodes, barrier walls formed on an upper surface of the dielectric layer to form discharge cells, phosphorous layers formed on surfaces of the barrier walls. Herein, two discharge sustaining electrodes are disposed in each discharge cell.

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Therefore, the address electrodes and discharge sustaining electrodes cause discharge in the discharge cells, and ultraviolet rays generated by the discharge excites the phosphorous layer, which then emits visible rays, thereby forming a desired image on a screen.

In general, in forming barrier walls of a rear plate of a PDP, the barrier walls are preliminary formed and are then baked, as disclosed in Japanese Patent Laid-Open Nos. P9-283018 and P9-102275.

When a PDP has been manufactured by attaching a conventional rear plate as described above to a front plate, the PDP has deteriorated electrical and optical properties due to characteristics of the manufacturing method thereof.

Disclosure of the Invention

Therefore, the present invention has been made in view of the above-mentioned problems, and it is an object of the present invention to provide a rear plate of a plasma display panel, which can improve electric

and optical characteristics of a PDP.

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According to an aspect of the present invention, there is provided a rear plate of a plasma display panel, the rear plate comprising: a glass substrate; electrodes formed in a shape of patterns on an upper surface of the glass substrate; a dielectric formed on upper surfaces of the electrode and the upper surface of the glass substrate; barrier walls formed in a shape of a pattern through etching on an surface of the dielectric layer; and phosphorous layers formed on side surfaces and bottom surfaces of barrier walls, wherein: each of the electrodes has a thickness of 2 to 8 μm and a specific resistance of 1.0 imes 10^{-6} to 5.0 imes 10^{-6} Ω cm; the dielectric layer is made from a first mixture which includes a first filler and at least one glass powder selected from among a first glass powder and a second glass powder, the first glass powder including PbO of 30 to 80 wt%, ZnO of 0 to 20 wt%, SiO_2 of 0 to 20 wt%, B_2O_3 of 5 to 40 wt%, Al_2O_3 of 0 0 to 5 $Na_2O+K_2O+Li_2O$ of wt%, BaO+CaO+MgO+SrO of 0 to 5 wt%, the second glass powder including Bi_2O_3 of 36 to 84 wt%, B_2O_3 of 5 to 28 wt%, PbO of 0 to 46 wt%, ZnO of 0 to 30 wt%, Al₂O₃ of 0 to 13 wt%, SiO_2 of 0 to 10 wt%, $Na_2O+K_2O+Li_2O$ of 0 to 5 wt%, and BaO+CaO+MgO+SrO of 0 to 3 wt%, each of the first and second glass powders having an average particle diameter of 1 to 10 μm , a softening temperature of 390 to 550 °C, and a thermal expansive coefficient of 63 \times 10^{-7} to 83 \times 10^{-7} /°C, the first filler having an average

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particle diameter of 0.01 to 10 μm , the dielectric 8 to 20, a layer having a dielectric constant of reflectance of 50 to 80%, an etching rate of 0.01 to um/min with respect to inorganic acid, thickness of 10 to 30 μm ; the barrier walls are made from a second mixture which includes a second filler, organic material, additives, and at least one glass powder selected from the group consisting of a third, fourth, and fifth glass powders, the third glass powder including ZnO of 0 to 48 wt%, SiO_2 of 0 to 21 wt%, B_2O_3 of 25 to 56 wt%, Al_2O_3 of 0 to 12 wt%, $Na_2O+K_2O+Li_2O$ of 0 38 wt%, and BaO+CaO+MgO+SrO of 0 to 15 wt%, the fourth glass powder including PbO of 25 to 65 wt%, ZnO of 0 to 35 wt%, SiO_2 of 0 to 26 wt%, B_2O_3 of 0 to 30 wt%, $Al_2O_3+SnO_2$ of 0 to 13 wt%, $Na_2O+K_2O+Li_2O$ of 0 to 19 wt%, BaO of 0 to 26 wt%, and CaO+MgO+SrO of 0 to 13 wt%, the fifth glass powder including PbO of 35 to 55 wt%, B_2O_3 of 18 to 25 wt%, ZnO of 0 to 35 wt%, BaO of 0 $SiO_2+Al_2O_3+SnO_2$ of 0 to wt%, $CoO+CuO+MnO_2+Fe_2O_3$ of 0 to 15 wt%, $Na_2O+K_2O+Li_2O$ of 0 to 19 wt%, and CaO+MgO+SrO of 0 to 13 wt%, the third glass powder having a softening temperature of 460 to 630 °C, a thermal expansive coefficient of 64×10^{-7} to 105×10^{-7} $^{7}/^{\circ}\text{C}$, and an average particle diameter of 0.5 to 17 μm , each of the fourth and fifth glass powders having a 390 to 550 °C, a thermal softening temperature of expansive coefficient of 63×10^{-7} to 110×10^{-7} /°C, and an average particle diameter of 0.5 to 17 μm, second filler having an average particle diameter of

0.01 to 10 $\mu\text{m}\text{,}$ the barrier walls being formed with a height of 100 to 180 μm by attaching a barrier wall layer formed in a shape of green tapes to an upper surface of the dielectric layer, firing the barrier wall layer together with the dielectric layer at a temperature between 400°C and 700 °C, and then etching the barrier wall layer, the barrier wall layer having a dielectric constant of 5 to 18, a reflectance of 40 to 80%, an etching rate of 1.0 to 50.0 $\mu m/min$ with respect to inorganic acid; each of the phosphorous layers has a thickness of 10 to 50 $\mu\text{m}\text{;}$ and a difference between the thermal expansive coefficients of the dielectric layer and the barrier wall layer has a percentage between 0 a difference between the softening 웧, and 10 temperatures of the dielectric layer and the barrier wall layer has a value between 0 and 20 °C.

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another aspect of the present According to invention, there is provided a rear plate of a plasma display panel, the rear plate comprising: substrate; electrodes formed in a shape of patterns on an upper surface of the glass substrate; a dielectric layer formed on upper surfaces of the electrode and the upper surface of the glass substrate; barrier walls formed in a shape of a pattern through etching on an upper surface of the dielectric layer; and phosphorous layers formed on side surfaces and bottom surfaces of the barrier walls, wherein: each of the electrodes has a thickness of 2 to 8 μm and a specific resistance of 1.0×10^{-6} to $5.0 \times 10^{-6}~\Omega \text{cm};$ the dielectric layer is

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made from a first mixture which includes first filler, organic material, additives, and at least one glass powder selected from among a first glass powder and a second glass powder, the first glass powder including PbO of 30 to 80 wt%, ZnO of 0 to 20 wt%, SiO_2 of 0 to 20 wt%, B_2O_3 of 5 to 40 wt%, Al_2O_3 of 0 to 12 wt%, $Na_2O+K_2O+Li_2O$ of 0 to 5 wt%, and BaO+CaO+MgO+SrO of 0 to 5 wt%, the second glass powder including $\mathrm{Bi}_2\mathrm{O}_3$ of 36 to 84 wt%, B_2O_3 of 5 to 28 wt%, PbO of 0 to 46 wt%, ZnO of 0 to 30 wt%, Al_2O_3 of 0 to 13 wt%, SiO_2 of 0 to 10 wt%, $Na_2O+K_2O+Li_2O$ of 0 to 5 wt%, and BaO+CaO+MgO+SrO 0 to 3 wt%, each of the first and second glass powders having an average particle diameter of 1 to 10 μ m, a softening temperature of 390 to 550 °C, and a thermal expansive coefficient of 63×10^{-7} to 83×10^{-7} 7/°C, the first filler having an average particle diameter of 0.01 to 10 $\mu m\text{,}$ the dielectric layer having a dielectric constant of 8 to 20, a reflectance of 50 to 80%, an etching rate of 0.01 to 1.0 $\mu m/min$ with respect to inorganic acid, and a thickness of 10 to 30 μm , the dielectric layer being formed in a shape of a green tape and then attached to upper surfaces of the electrodes; the barrier walls are made from a second organic filler, includes a second mixture which material, additives, and at least one glass powder selected from the group consisting of a third, fourth, glass powder the third powders, glass fifth including ZnO of 0 to 48 wt%, SiO $_2$ of 0 to 21 wt%, B_2O_3 of 25 to 56 wt%, Al_2O_3 of 0 to 12 wt%, $Na_2O+K_2O+Li_2O$ of 0

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to 38 wt%, and BaO+CaO+MgO+SrO of 0 to 15 wt%, the fourth glass powder including PbO of 25 to 65 wt%, ZnO of 0 to 35 wt%, SiO_2 of 0 to 26 wt%, B_2O_3 of 0 to 30 wt%, $Al_2O_3+SnO_2$ of 0 to 13 wt%, $Na_2O+K_2O+Li_2O$ of 0 to 19 wt%, BaO of 0 to 26 wt%, and CaO+MgO+SrO of 0 to 13 wt%, the fifth glass powder including PbO of 35 to 55 wt%, B_2O_3 of 18 to 25 wt%, ZnO of 0 to 35 wt%, BaO of 0 0 to $SiO_2+Al_2O_3+SnO_2$ of wt%, to CoO+CuO+MnO₂+Fe₂O₃ of 0 to 15 wt%, Na₂O+K₂O+Li₂O of 0 to 19 wt%, and CaO+MgO+SrO of 0 to 13 wt%, the third glass powder having a softening temperature of 460 to 630 °C, a thermal expansive coefficient of 64×10^{-7} to 105×10^{-7} $^{7}/^{\circ}\text{C}$, and an average particle diameter of 0.5 to 17 μm , each of the fourth and fifth glass powders having a softening temperature of 390 to 550 °C, a thermal expansive coefficient of 63×10^{-7} to 110×10^{-7} /°C, and an average particle diameter of 0.5 to 17 μm , second filler having an average particle diameter of 0.01 to 10 $\mu\text{m}\text{,}$ the barrier walls being formed with a height of 100 to 180 μm by attaching a barrier wall layer formed in a shape of green tapes to an upper surface of the dielectric layer, firing the barrier wall layer together with the dielectric layer at a temperature between 400°C and 700 °C, and then etching the barrier wall layer, the barrier wall layer having a dielectric constant of 5 to 18, a reflectance of 40 to 80%, and an etching rate of 1.0 to 50.0 $\mu m/min$ with respect to inorganic acid; each of the phosphorous layers has a thickness of 10 to 50 μm ; and a difference between the thermal expansive coefficients of the dielectric layer and the barrier wall layer has a percentage between 0 and 10 %, and a difference between the softening temperatures of the dielectric layer and the barrier wall layer has a value between 0 and 20 °C.

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According to still another aspect of the present invention, there is provided a rear plate of a plasma display panel, the rear plate comprising: substrate; electrodes formed in a shape of patterns on an upper surface of the glass substrate; a dielectric layer formed on upper surfaces of the electrode and the upper surface of the glass substrate; barrier walls formed in a shape of a pattern through etching on an upper surface of the dielectric layer; and phosphorous layers formed on side surfaces and bottom surfaces of the barrier walls, wherein: each of the electrodes has a thickness of 2 to 8 μm and a specific resistance of 1.0×10^{-6} to $5.0 \times 10^{-6} \Omega$ cm; the dielectric layer is made from a first mixture which includes а filler, organic material, additives, and at least one glass powder selected from among a first glass powder and a second glass powder, the first glass powder including PbO of 30 to 80 wt%, ZnO of 0 to 20 wt%, SiO₂ of 0 to 20 wt%, B_2O_3 of 5 to 40 wt%, Al_2O_3 of 0 to 12 wt%, Na₂O+K₂O+Li₂O of 0 to 5 wt%, and BaO+CaO+MgO+SrO of 0 to 5 wt%, the second glass powder including Bi_2O_3 of 36 to 84 wt%, B_2O_3 of 5 to 28 wt%, PbO of 0 to 46 wt%, ZnO of 0 to 30 wt%, Al_2O_3 of 0 to 13 wt%, SiO_2 of 0 to 10 wt%, $Na_2O+K_2O+Li_2O$ of 0 to 5 wt%, and BaO+CaO+MgO+SrO

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of 0 to 3 wt%, each of the first and second glass powders having an average particle diameter of 1 to 10 μ m, a softening temperature of 390 to 550 °C, and a thermal expansive coefficient of 63×10^{-7} to 83×10^{-7} 7/°C, the first filler having an average particle diameter of 0.01 to $10 \mu m$, the dielectric layer having a dielectric constant of 8 to 20, a reflectance of 50 to 80%, an etching rate of 0.01 to 1.0 $\mu\text{m/min}$ with respect to inorganic acid, and a thickness of 10 to 30 um, the dielectric layer being formed in a shape of a green tape; the barrier walls are made from a second filler, mixture .which includes a second material, additives, and at least one glass powder selected from the group consisting of a third, fourth, glass powder fifth glass powders, the third including ZnO of 0 to 48 wt%, SiO_2 of 0 to 21 wt%, B_2O_3 of 25 to 56 wt%, Al₂O₃ of 0 to 12 wt%, Na₂O+K₂O+Li₂O of 0 38 wt%, and BaO+CaO+MgO+SrO of 0 to 15 wt%, the fourth glass powder including PbO of 25 to 65 wt%, ZnO of 0 to 35 wt%, SiO_2 of 0 to 26 wt%, B_2O_3 of 0 to 30 wt%, $Al_2O_3+SnO_2$ of 0 to 13 wt%, $Na_2O+K_2O+Li_2O$ of 0 to 19 wt%, BaO of 0 to 26 wt%, and CaO+MgO+SrO of 0 to 13 wt%, the fifth glass powder including PbO of 35 to 55 wt%, B₂O₃ of 18 to 25 wt%, ZnO of 0 to 35 wt%, BaO of 0 0 to. wt%, $SiO_2+Al_2O_3+SnO_2$ of to 16 $CoO+CuO+MnO_2+Fe_2O_3$ of 0 to 15 wt%, $Na_2O+K_2O+Li_2O$ of 0 to 19 wt%, and CaO+MgO+SrO of 0 to 13 wt%, the third glass powder having a softening temperature of 460 to 630 °C, a thermal expansive coefficient of 64×10^{-7} to 105×10^{-7}

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 $^{7}/^{\circ}$ C, and an average particle diameter of 0.5 to 17 μ m, each of the fourth and fifth glass powders having a softening temperature of 390 to 550 °C, a thermal expansive coefficient of 63×10^{-7} to $110 \times 10^{-7}/^{\circ}\text{C}$, and an average particle diameter of 0.5 to 17 μm, second filler having an average particle diameter of 0.01 to 10 μm ; each of the phosphorous layers has a thickness of 10 to 50 μm ; and a difference between the thermal expansive coefficients of the dielectric layer and the barrier wall layer has a percentage between 0 and a difference between the softening 응. temperatures of the dielectric layer and the barrier wall layer has a value between 0 and 20 °C, wherein a barrier wall layer formed in a shape of green tapes, dielectric constant of 5 a has reflectance of 40 to 80%, and an etching rate of 1.0 to with respect to inorganic acid, μm/min integrated with the dielectric layer to form lamination of dielectric layer/ barrier wall layer, and the lamination of dielectric layer/ barrier wall layer is attached to the upper surfaces of the electrodes and the glass substrate, is baked at a temperature between 400°C and 700 °C, and is then etched, so that barrier walls are formed with a height of 100 to 180 μm.

Herein, each of the barrier walls has at least two different layers having different etching rates with respect to inorganic acid.

In a rear plate of a plasma display panel

according to the present invention, a dielectric layer or a barrier wall layer is formed by forming slurry in a tape of a green tape and then attaching the green tape to upper surfaces of electrodes and a glass substrate. Therefore, a PDP employing a rear plate according to the present invention has superior electric and optical characteristics.

Brief Description of the Drawings

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The foregoing and other objects, features and advantages of the present invention will become more apparent from the following detailed description when taken in conjunction with the accompanying drawings in which:

FIG. 1 is a sectional view of a rear plate of a plasma display panel according to a first embodiment of the present invention;

FIG. 2 is a sectional view of a rear plate of a plasma display panel according to a second embodiment of the present invention; and

FIG. 3 is a sectional view of a rear plate of a plasma display panel according to a third embodiment of the present invention.

Best Mode for Carrying Out the Invention

Hereinafter, a rear plate of a plasma display panel according to preferred embodiments of the present invention will be described in detail with reference to the accompanying drawings. FIG. 1 is a sectional view of a rear plate of a plasma display panel according to a first embodiment of the present invention.

As shown in FIG. 1, a rear plate 100 of a plasma display panel (hereinafter, referred to as "PDP") according to the present embodiment includes a glass substrate 110, electrodes 120 formed in a shape of a pattern and spaced at a predetermined interval from each other on an upper surface of the glass substrate 110, a dielectric layer 130 formed on upper surfaces of the electrode 120 and the upper surface of the glass substrate 110, barrier walls 140 formed on an upper surface of the dielectric layer 130 and spaced a predetermined interval from each other, and phosphorous layers 150 formed on side surfaces and bottom surfaces of the barrier walls 140.

Since the barrier walls 140 is formed through etching, the barrier walls must have a proper etching rate for etching solution and the electrodes 120 and the dielectric layer 130 must have resistance to the etching solution. In order to meet the requirements described above, each of the functional layers of the rear plate 100 according to the present embodiment has a specific composition, which will be described hereinafter.

First embodiment

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In the rear plate 100 according to the first embodiment of the present invention, the dielectric

layer 130 is formed by a screen printing method, the barrier walls are formed in a shape of green tapes, and then the dielectric layer 130 and the barrier walls are simultaneously baked. This process will be described in detail hereinafter.

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The electrodes 120 formed on the upper surface of the glass substrate has a thickness of $2 \sim 8 \, \mu \mathrm{m}$. That is, photosensitive paste for the electrodes, which has a specific resistance of 2.5 x 10^{-6} to 4.0 x $10^{-6}\Omega\,\mathrm{cm}$, is surface of the the upper screen-printed on and is then subjected to dried, substrate 110, is thereby forming firing, and photolithography When the electrodes have a specific electrodes 120. resistance of lower than 2.5 \times 10⁻⁶, the low resistance enables the electrodes to process an address signal However, the electrodes must be made without noise. from gold or silver with high purity, which increases the manufacturing cost for the electrodes. In contrast, when the electrodes have a specific resistance larger than $4 \times 10^{-6} \ \Omega \, \text{cm}$, such problems as increase of an address driving voltage are caused.

The dielectric layer 130 is made from mixture of a first filler and at least one glass powder selected from among a first glass powder and a second glass powder. The dielectric layer 130 has a thickness of 10 to 30 μm .

The first glass powder comprises PbO of 30 to 80 wt%, ZnO of 0 to 20 wt%, SiO $_2$ of 0 to 20 wt%, B $_2$ O $_3$ of 5 to 40 wt%, Al $_2$ O $_3$ of 0 to 12 wt%, Na $_2$ O+K $_2$ O+Li $_2$ O of 0 to 5

wt%, and BaO+CaO+MgO+SrO of 0 to 5 wt%. The second glass powder comprises Bi_2O_3 of 36 to 84 wt%, B_2O_3 of 5 to 28 wt%, PbO of 0 to 46 wt%, ZnO of 0 to 30 wt%, Al_2O_3 of 0 to 13 wt%, SiO_2 of 0 to 10 wt%, $Na_2O+K_2O+Li_2O$ of 0 to 5 wt%, and BaO+CaO+MgO+SrO of 0 to 3 wt%. The first filler includes at least one selected from the group consisting of TiO_2 , ZrO_2 , ZnO_3 , Al_2O_3 , BN, mullite, and MgO.

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Each of the first and second glass powders has a softening temperature of 390 to 550 °C. When their 390 °C, smaller than softening temperature is dielectric layer 130 may flow in steps of firing the phosphorous layers and attaching the front plate and the rear plate of the PDP to each other after the barrier walls 140 are formed, thereby deteriorating measurements of the in t.he correctness contrast, when the softening temperature is larger than 550 °C, the firing temperature of the dielectric layer 130 becomes so high as to change the measurements of the glass substrate 110, thereby causing it difficult to control the measurements of the glass substrate 110.

It is preferred that each of the first and second glass powders has an average particle diameter of 1 to 10 μm . When each of the first and second glass powders has an average particle diameter of less than 1 μm , they have a reduced workability. In contrast, when each of the first and second glass powders has an average particle diameter of more than 10 μm , the dielectric layer 130 is not sufficiently compacted while being

baked, so that the dielectric layer 130 may be porous.

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Also, each of the first and second glass powders preferably has a thermal expansive coefficient of 63 x 10^{-7} to 83 × 10^{-7} /°C. When the thermal expansive coefficient is smaller than 63×10^{-7} /°C, the glass substrate 110 may be convexly bent. In contrast, when the thermal expansive coefficient is larger than 83 imes 10^{-7} /°C, the glass substrate 110 may be concavely bent or the surface of the dielectric layer 130 may crack. However, even when each of the first and second glass powders preferably has a thermal expansive coefficient of 95 \times 10⁻⁷/°C, the thermal expansive coefficient can be lowered to 83 $\times 10^{-7}$ /°C by mixing a proper amount of the first filler with the first and second glass powders. Therefore, it will do if each of the first and second glass powders preferably has a thermal expansive coefficient of 63×10^{-7} even up to 95×10^{-7} /°C.

It is preferred that each of the first and second glass powders has a dielectric constant of 11 to 26. When the dielectric constant of the dielectric layer 130 is smaller than 11, it is difficult to transfer a of the electrode 120 to a discharge space defined by the barrier walls 140. In contrast, when the dielectric constant of the dielectric layer 130 larger than 26, the PDP has too slow a response speed when the PDP is driven. Meanwhile, when each of the powders has а dielectric second glass and constant of at least 6, the dielectric constant of the dielectric layer 130 can be elevated up to 11 by means of the first filler. Therefore, it is also preferred that each of the first and second glass powders has a dielectric constant of 6 to 26.

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The first filler preferably has an average particle diameter of 0.01 to 10 μm . Further, it is preferred that a volumetric ratio of the first filler with respect to the glass powder in the dielectric layer is 0.05 to 0.67. When the volumetric ratio is than 0.05, the dielectric layer reflectance of at most 50%, thereby preventing the PDP from employing a dielectric layer having a reflectance of at least 50% which is necessary in order to enable the PDP to have an improved brightness. Further, in the case in which the volumetric ratio is more than 0.67, when the softening temperature of the glass powder is low, the dielectric constant is high and thus the response seed is slow. In contrast, when the softening temperature of the glass powder is high, the degree of firing of the dielectric layer 130 deteriorates, that it is difficult for the dielectric layer 130 to have a resistance to etching and the dielectric layer 130 has a dielectric constant of at most 11.

The dielectric layer 130 having the ingredients as described above has a dielectric constant of 8 to 20, a reflectance of 50 to 80%, and an etching rate of 0.1 to $1.0~\mu\text{m/min}$ with respect to inorganic acid. When the etching rate of the dielectric layer 130 is smaller than 0.1 $\mu\text{m/min}$, the firing temperature of the dielectric layer 130 may rise above 700 °C, thereby

deforming the glass substrate 110. In contrast, when the etching rate is larger than 1.0 μ m/min, the powder has a reduced resistance to etching, so that even the dielectric layer 130 and the electrodes 120 may be etched when the barrier wall 140 is etched. When the electrode 120 has been damaged by etching, the electric resistance of the electrode 120 increases.

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The first filler can be classified into two kinds of oxides, which have weak and strong chemical durability with respect to acid-based etching solution, respectively. The first kind of oxide having a weak chemical durability with respect to acid-based etching solution reacts with glass powder while it is baked, thereby deteriorating the chemical durability of the reacted glass powder. In contrast, the second kind of oxide having a strong chemical durability with respect to acid-based etching solution reacts with glass powder while it is baked, thereby increasing the chemical durability of the reacted glass powder.

Further, when the dielectric layer 130 includes too much first filler, quantity of the first filler, which does not react with the oxide, increases, so that firing strength deteriorates. Therefore, it is preferred that a ratio of volume of the first filler with respect to volume of the glass powder in the dielectric layer 130 is not larger than 0.67. The less the quantity of the first filler is, the more the white degree of the dielectric layer 130 deteriorates. However, since some PDPs may have a dielectric layer

130 with an unlimited white degree, it is unnecessary to define a lower limit of the ratio of volume of the first filler with respect to volume of the glass powder in the dielectric layer 130.

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The dielectric layer 130 may have defect due to either repetition of printing and drying processes or The defect due to screen plate screen plate making. making include irregular thickness of meshes, uniform surface state of meshes, stains of meshes, etc., which may cause defect such as pinholes or height difference on the dielectric layer 130. Further, dielectric layer 130 may be of the material of the end portions under insufficiently filled electrodes 120 due to a curl phenomenon in which the 120 formed through end portions of the electrodes photolithography and firing are curled up while they are being baked. Then, bubbles may be generated between the electrodes 120 and the dielectric layer 130 to voltage, thereby causing resistance the insulation breaking, while a PDP operates. Therefore, in forming the dielectric layer 130, either a printing method or a green tape attachment method, which will be described later, must be employed according to material or characteristics of its shape.

The barrier walls 140 are formed on the upper surface of the dielectric layer 130. Specifically, a slurry is formed in a shape of green tapes having a predetermined thickness and is then attached to the upper surface of the dielectric layer 130. Then, the

attached green tapes are subjected to photolithography and etching, thereby the barrier walls 140 having a shape of patterns.

The barrier wall 140 is made in a shape of green tapes by adding organic material and additive to mixture of a second filler and at least one glass powder selected from the group consisting of the third, fourth, and fifth glass powders.

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The third glass powder comprises ZnO of 0 to 48 wt%, SiO_2 of 0 to 21 wt%, B_2O_3 of 25 to 56 wt%, Al_2O_3 of 12 wt%, $Na_2O+K_2O+Li_2O$ of 0 to 38 wt%, BaO+CaO+MgO+SrO of 0 to 15 wt%. The fourth glass powder comprises PbO of 25 to 65 wt%, ZnO of 0 to 35 wt%, SiO₂ of 0 to 26 wt%, B_2O_3 of 0 to 30 wt%, $Al_2O_3+SnO_2$ of 0 to 13 wt%, $Na_2O+K_2O+Li_2O$ of 0 to 19 wt%, BaO of 0 to 26 wt%, and CaO+MgO+SrO of 0 to 13 wt%. The fifth glass powder comprises PbO of 35 to 55 wt%, B₂O₃ of 18 to 25 ZnO of 0 to 35 wt%, BaO of 0 to 16 wt%, $SiO_2+Al_2O_3+SnO_2$ of 0 to 9 wt%, $CoO+CuO+MnO_2+Fe_2O_3$ of 0 to 15 wt%, Na₂O+K₂O+Li₂O of 0 to 19 wt%, and CaO+MgO+SrO of 0 to 13 wt%. The second filler includes at least one selected from the group consisting of TiO2, ZrO2, ZnO, Al_2O_3 , BN, mullite, and MgO.

Herein, the third glass powder has a softening temperature of 460 to 630 °C, and each of the fourth and fifth glass powders has a softening temperature of 390 to 550 °C. In the case where the softening temperature is smaller than 460 °C and 390 °C, respectively, when the phosphorous layers 150 are baked after the barrier

walls 140 are formed or after the front and rear plates are attached to each other, the barrier walls 140 may be deformed so that the barrier walls 140 may have much irregular heights and their upper portions may have much irregular widths. In contrast, in a case where the softening temperature is larger than 630 °C and 550 °C, respectively, the firing temperature of the barrier wall 140 increases, thereby causing it difficult to control the measurements of the glass substrate 110.

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The third glass powder has a thermal expansive coefficient of 64×10^{-7} to 105×10^{-7} /°C, and each of the fourth and fifth glass powders preferably has a thermal expansive coefficient of 63×10^{-7} to 110×10^{-7} 7/°C. When the thermal expansive coefficient is smaller than 63 \times 10⁻⁷/°C and 63 \times 10⁻⁷/°C, respectively, the glass substrate 110 may be convexly bent. In contrast, when the thermal expansive coefficient is larger than 105×10^{-7} /°C or 110×10^{-7} /°C, respectively, the glass substrate 110 may be concavely bent or the surface of the glass substrate 110 may crack. However, since the thermal expansive coefficient can be changed adjusting the amount of the filler in the barrier wall 140, each of the third, fourth, and fifth glass powders may preferably have a thermal expansive coefficient of 63×10^{-7} even up to 110×10^{-7} /°C.

Each of the third, fourth, and fifth glass powders has an average particle diameter of 0.5 to 17 $\mu m\,.$ When the glass powder has an average particle diameter of smaller than 0.5 $\mu m\,,$ it is difficult to make paste for

the barrier wall from the glass powder. In contrast, when the conductive metal powder has an average particle diameter of larger than 17 μm , it is difficult to enable the barrier walls to be sufficiently compact through firing after forming the barrier walls.

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Each of the third, fourth, and fifth glass powders has a dielectric constant of 5 to 20. In the case where the dielectric constant is smaller than 5, a drive voltage characteristic is deteriorated when a manufactured PDP is driven. In contrast, in the case where the dielectric constant is larger than 20, crosstalk and erroneous discharge may occur when the manufactured PDP is driven.

Further, the second filler has an average particle diameter of at most 10 μm . Also, a volumetric ratio of the first filler with respect to the glass powder for the barrier walls is 0.05 to 0.67, which will be described later.

Organic material and additive are added to the material for the barrier walls as described above, so as to form a slurry with a viscosity of 500 to 40000 cP (centi-poise) in a shape of green tapes, barrier walls. Then, forming preliminary the preliminary barrier walls in a shape of green tapes are attached to the upper surface of the dielectric layer 130 through lamination, and are then simultaneously baked together with the dielectric layer 130 at a temperature above 400 °C. Herein, it is preferred that the preliminary barrier walls in a shape of green tapes have a thickness of 100 o 180 μm.

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In order to simultaneously bake the dielectric layer 130 and the barrier walls, a difference between the thermal expansive coefficients of them must have a value of at most 10%, and a difference between the softening temperatures of them must have a value of at most 20°C. Ιf the difference between the thermal expansive coefficients of them has a value larger than 10%, the dielectric layer 130 and the barrier walls may be separated from each other, thereby allowing bubbles between them, when they have formed simultaneously baked. Further, the glass substrate 110 may be bent due to the difference between the thermal expansive coefficients of them, thereby preventing the rear plate from being attached to the front plate.

Further, when the difference between the softening temperatures of them has a value larger than 20°C, end portions of the dielectric layer 130 and the barrier walls may be curled up or may come off, thereby allowing bubbles to be formed between them. When too interface between in many bubbles exist an dielectric layer 130 and the barrier walls, each of the dielectric layer 130 and the barrier walls may have a structure, thereby having internal sparse fragility and deteriorated strength. Further, when too between interface exist in an bubbles dielectric layer 130 and the barrier walls, the bubbles may come into the dielectric layer 130 and the barrier walls while the dielectric layer 130 and the barrier walls are baked, so that the dielectric layer 130 and the barrier walls may have deteriorated properties and insulation breaking may occur while a PDP operates.

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In order to prepare the material for the barrier walls in a form of slurry, organic materials additives are necessary. The organic materials include a binding agent which provides strength to the barrier walls, a solvent which dissolves the material of the and provides fluidity necessary barrier walls milling and casting to the barrier walls, plasticizer which improves workability of the barrier The additives include a defoaming agent for walls. reducing generation of bubbles, a dispersing agent for aiding dispersion of inorganic material, dyes, lubricating oil.

The binding agent includes at least one selected Polyvinyl group consisting of from the Polyvinyl acetate, Poly Polyvinyl alcohol, Metaacrylate, Poly ethyl acrylate, Poly acrylic acid, Hydroxyethyl cellulose, Cellulose, cellulose, Carboxymethyl cellulose, Acrylic ester, and The solvent includes at least Ammonium Polyacrylate. group consisting of selected from the one n-Butyl alcohol, Toluene, Water, alcohol, alcohol, n-Propyl alcohol, Isopropyl alcohol, Ethylene Benzaldehide, Ethylacetate, Cyclohexane, Glycol, Isopropyl acetate, n-Octyl alcohol, Benzyl alcohol, Glycerol, Acetone, Methyl Ethyl Keton, Propionic acid, n-Octanoic acid, n-Hexane, O-Xylene, MIBK, Xylene, and Butanyl. The plasticizer includes at least one selected from the group consisting of Water, Ethylene Glycol, Diethylene Glycol, Tetraethylene glycol, Glycerine, Dimethyl phtalate, Dibutyl phtalate, Benzyl butyl phthalate, poly propylene glycol, Phosphate, Phthalate, Glycol ether, and Polyethylen glycol.

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As the additives, typical additives are used.

The binding agent must experience a complete thermal decomposition through the drying and firing the binding agent is not process. Ιf decomposed, carbon residue may exist in the barrier greatly decreasing an insulation walls, thereby strength of the barrier walls. The solvent is selected in consideration of viscosity of slurry and drying speed according to the thickness of the green tapes and solubility and speed of dissolution casting, adhesive agent and other organic materials, etc. The. selected in consideration plasticizer must be compatibility of the plasticizer with the binding If a plasticizer shows an incompatibility with respect to the binding agent according to temperature increase, the plasticizer escapes out of the green tapes during the drying process, so that the green tapes have fragility. The organic material is selected in consideration of properties such as viscosity in milling, viscosity in casting, thickness of the green tapes, strength of the green tapes, percentage of elongation, and workability. When the quantity of the organic material is too much, defoamation process must be performed for long time. In contrast, when the quantity of the organic material is too little, an efficiency of milling for preparing the slurry deteriorates.

As shown in FIG. 2, each barrier wall 245 may 5 include a plurality of wall layers 245-1, 245-2, 245-(n-1), 245-n which are prepared from different materials having different etching rates to inorganic acid. Herein, if the multiple wall layers 245-1, 245-2,..., $245_{-(n-1)}$, 245_{-n} constituting the barrier wall 245 are 10 named first, second,..., $(n-1)^{th}$, and n^{th} wall layers, respectively, the (n-1)th wall layer has an etching rate with respect to inorganic acid, which is larger than or equal to that of the nth wall layer. As a result, when the barrier wall 245 is formed through etching, side 15 surfaces of the barrier wall 245 can be formed nearly vertically, thereby forming a rectangular discharge space.

Further, each of the wall layers 245_{-1} , 245_{-2} ,..., $245_{-(n-1)}$, 245_{-n} must have a thickness corresponding to 5% 20 to 95% of the entire thickness of the barrier wall 245. If any of the wall layers has a thickness, which is either smaller than 5% or larger than 95% of the entire thickness of the barrier wall 245, the thickness of that wall layer is too small or too large to have an 25 effect by the adjustment of etching rate as described above, thereby making it useless to form the barrier wall 245 from at least two kinds of different materials.

When barrier walls are formed in a shape of green which organic material tapes from mixture in additives are added to the material of the barrier which has the composition and properties walls, described above according to the first embodiment of the barrier walls invention, present dielectric constant of 5 to 18, a reflectance of 40 to 80%, and an etching rate of 1.0 to 50.0 μ m/min.

Further, the phosphorous layers 150 include red, green, and blue phosphorous layers formed on side and bottom surfaces of the barrier walls 140, each of the phosphorous layers having a thickness of at least 10 µm.

15 Second embodiment

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FIG. 2 is a sectional view of a rear plate of a plasma display panel according to the second embodiment of the present invention.

As shown, a dielectric layer 230 and barrier walls 245 each are arranged in a shape of green tapes, the dielectric layer 230 is formed on upper surfaces of an electrode 220 and a glass substrate 210, and then the barrier walls 245 are formed on an upper surface of the plate 200 230, that a rear dielectric layer so according to the second embodiment of the present invention is completed.

The electrode 220 according to the second embodiment is the same as the electrode according to the first embodiment, and the dielectric layer 230

according to the second embodiment is made from the same material as that of the dielectric layer 130 according to the first embodiment. However, in forming the dielectric layer 230 according to the embodiment, organic material and additives are added to material of the dielectric layer 130 according to the first embodiment, which is then formed in a shape of green tapes and attached to the upper surfaces of the electrode 220 and the glass substrate 210. Further, the barrier walls 245 according to the second embodiment is formed on the upper surface of the dielectric layer 230 in the same manner as that according to the first layer 230 the dielectric and embodiment. and barrier walls 245 are simultaneously baked at temperature above 400°C as those according to the first embodiment.

The other constructions according to the second embodiment are the same as those according to the first embodiment.

20 Third embodiment

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FIG. 3 is a sectional view of a rear plate of a plasma display panel according to the third embodiment of the present invention.

As shown, composition and characteristics of each functional layer of a rear plate according to the third embodiment of the present invention is the same as the composition and characteristics of each functional layer of the rear plate according to the second embodiment of the present invention. In description of

only the differences between them, a dielectric layer 330 and barrier walls 345 are prepared in a shape of green tapes having a thickness of 10 to 30 μ m and 100 to 180 μ m, respectively, and are integrated with each other. Thereafter, the dielectric layer 330 is attached to upper surfaces of electrodes 320 and a glass substrate 310. Then, they are baked at a temperature above 400°C, so that the dielectric layer 330 and the barrier walls 345 are completed.

The other constructions according to the third embodiment are the same as those according to the second embodiment.

The etching rate described in the first, second, and third embodiments is defined by an equation, etching rate = {(M1-M2)/6.25} × 100. In this equation, M1 implies mass of a substrate having a size of 2.5 cm × 2.5 cm, on the entire surface of which material for the dielectric layer or the barrier walls has been applied and then baked. M2 implies mass of the substrate, measured after the substrate is wet-etched for two minutes, is washed for one minute by ultrasonic wave and then for one minute by flowing water, and is then dried.

Next, measured properties of each functional layer of the rear plate manufactured as described above will be described.

Experiment 1

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EPH-200TR5611 photosensitive electrode paste

having a specific resistance of 2.7 x $10^{-6}\Omega$ cm, made by company of with a Taiyo Ink Japan, was applied thickness of $4\sim 6\mu\mathrm{m}$ on an upper surface of a glass substrate by means of a polyester screen Mask of #200 mesh and was then dried for fifteen minutes at 90°C, thereby forming an electrode layer. Thereafter, the electrode layer formed on the glass substrate exposed to light and was then developed, electrodes having a shape of patterns were formed. the exposure step, the electrode layer was exposed to light of 500 mJ emitted by a mirror reflected parallel beam illuminator (MRPBI) equipped with a mercury lamp. in the development step, solution containing sodium carbonate of 0.4 wt% at a temperature of 30°C was sprayed for thirty seconds at a pressure of 0.2 Mpa, and then pure water at 25°C was sprayed for thirty seconds at a pressure of 0.1 Mpa onto the electrode Then, the electrodes dried after being substrate. developed were baked for fifteen minutes at a maximum temperature of 550°C.

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A dielectric layer with a thickness of 22 μm was formed on upper surfaces of the electrodes through screen printing using a SUS screen Mask of #200 mesh, and was then dried for ten minutes at 120°C. Table 1 shows composition of the dielectric layer.

Table 1
Composition of the dielectric layer according to experiment 1:

Class		Gradie	nts of g	lass po	wder (w	t%)		1 st
	PbO	SiO ₂	в203	Al ₂ O ₃	ZnO	NaO	BaO	filler
Dielec-	43.5	16	8	2.5	29	1		TiO ₂ +
tric								ZnO ₂ +
layer								Al ₂ O ₃

Glass powder of the dielectric layer having the composition shown in table 1 has a softening temperature of 460°C. When the dielectric layer has been baked for fifteen minutes at a maximum temperature of 530°C, the dielectric layer has a dielectric constant of 12.5, a reflectance of 70%, an etching rate of 0.5 μ m/min with respect to inorganic acid.

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The barrier walls were formed in a shape of green tapes with three layers and were then laminated on the upper surface of the dielectric layer. Table 2 shows composition of each layer of the barrier walls.

Table 2

15 Composition of each layer of the barrier walls according to experiment 1:

according to experiment 1:											
Cl	ass		Gradients of glass powder (wt%)								
		PbO	ZnO	SiO ₂	B ₂ O ₃	Al ₂ O ₃	Li ₂ O+	BaO	CaO+		
						+ZnO ₂	Na ₂ O+		MgO+		
							K₂O		SrO		
Parti-	1 st	40	22	6	18	2	12	0	1	TiO ₂ +ZnO ₂	
tion	layer									+Al ₂ O ₃	
wall	2 nd	41	30	5	18	2	2	0	2	ZrO ₂ +Al ₂ O ₃	
	layer										

3 rd	55	20	0	16	1	5	1	2	TiO ₂ +ZrO ₂
layer									+Al ₂ O ₃

In forming the barrier walls in a shape of green B-48, binders having B - 44and which are different molecular weights from among PolyMethyl Meta Acrylate-series (PMMA-series) binders manufactured by Rohm and Hass company, were employed, mixture of ethyl alcohol and toluene by 1:1 was employed as solvent, and employed as plasticizer. phtalate was a dimethyl Further, menhaden fish oil was employed as a dispersing agent, and stearic acid was employed as a lubricating agent. Herein, a binder of 6 wt%, a solvent of 30 wt%, a plasticizer of 8 wt%, a dispersing agnet of 1 wt%, and a lubricating agent of 0.3 wt% were added in the powder mixture of 100 wt% for the barrier walls, which glass powder and filler are mixed.

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After the additives described were added, barrier walls were formed in a shape of green tapes with three layers by means of a tape caster. barrier wall was solidified to have a total thickness of 196 µm, in which a thickness ratio of (the first layer): (the third layer) layer): (the second Thereafter, the barrier walls having a 1:(0.9):(0.8). shape of green tapes were attached to the upper surface of the dielectric layer through laminating by a roller at a temperature of 105°C and a pressure of 0.3Mpa, and were then baked together with the dielectric layer at a maximum temperature of 530°C for 15 minutes. Then, each

of the formed barrier walls were formed to have a thickness of 150 $\mu \text{m}\,.$

Table 3 shows properties of the barrier walls formed as described above.

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Table 3
Measured properties of each layer of the barrier wall according to experiment 1:

accor	according to experiment 1:										
Cla	Class		Thermal	Average	Dielectric	Reflection	Etching				
		ing	expansive	particle	constant	ratio(%)	rate				
		temper-	coeffici-	diameter			(μm/Min)				
		ature	ent	(tau)							
			(x 10 ⁻⁷ /℃)								
	1 st	40	22	6	18	2	12				
Parti	layer			<u> </u>							
-tion	2 nd	41	30	5 ·	18	2	2				
wall	layer					· .					
	3 rd	55	20	0	16	1	5				
	layer	:									

Photosensitive material was applied on the upper surfaces of the barrier walls, was exposed to light by means of a photo mask, and was then developed. Thereafter, inorganic acid was sprayed onto the developed photosensitive material at a pressure of 2 kgf/cm², so that the barrier walls were completely formed in a shape of patterns through a selective wet etching. Then, each barrier wall had an uppermost portion having a width of 50 μ m and a lowermost portion having a width of 120 μ m.

Thereafter, red, green, and blue phosphors were printed with a thickness of 17 μm on side and bottom surfaces of the barrier walls, thereby forming phosphorous layers covered on the barrier walls.

Table 4 shows properties of PDPs employing a rear plate according to experiment 1 and a conventional rear plate, respectively.

Table 4

10 Measured properties of PDPs employing a rear plate according to experiment 1 and a conventional rear plate:

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	Class	PDP	PDP
		employing	employing
		conventional	rear plate
		rear plate	of
	Mark I		experiment 1
	Pitch	250 <i>µ</i> m	250 <i>µ</i> m
Number	of firings of rear plate	4 times	3 times
	Discharge space	100%	106€
Optical	White Peak brightness	100%	132%
properties	Color temperature(K)	8500	8802
	Contrast	100%	128%
Electrical	Voltage margin	100%	145%
properties	Power consumption	100%	89%
	Module efficiency	100%	125%
reliability	High temp./low temp. erroneous	No	No
	discharge		

	vibration/drop test	No	No	
		progressive	progressive	
		defect	defect	
Other	noise (dB)	100%	75%	
properties		•		

As apparent from table 4, a PDP employing a rear 1 of the present according to experiment invention has shown improvement in comparison with a PDP employing a conventional rear plate, which includes 6% increase of discharge space, 32% increase of white 302k increase of color temperature, brightness, increase of contrast, 45% of 11% voltage margin, 25% increase of PDP decrease of power consumption, efficiency, and 25% decrease of noise. In table 4, "Pitch" implies a distance between centers of adjacent two barrier walls.

Experiment 2

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Electrodes in experiment 2 are the same as the electrodes in experiment 1, excepting that the firing temperature in experiment 2 is 570°C.

An electrode layer formed on a glass substrate was exposed to light and developed, so that electrodes having a shape of patterns were formed. In the exposure step, the electrode layer was exposed to light of 500 mJ emitted by a mirror reflected parallel beam illuminator equipped with a mercury lamp. Also, in the development step, solution containing sodium carbonate

of 1.0 wt% at a temperature of 30°C was sprayed for thirty seconds at a pressure of 0.2 Mpa, and then pure water at 30°C was sprayed for thirty seconds at a pressure of 0.1 Mpa onto the electrode substrate. Then, the electrodes dried after being developed were baked for fifteen minutes at a maximum temperature of 570°C.

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Thereafter, the dielectric layer was formed in a form of a green tape and was then laminated on the upper surfaces of the electrodes. Table 5 shows composition of the dielectric layer.

Table 5
Composition of the dielectric layer in experiment 2

Class			Glass	Filler				
	PbO	SiO ₂	B ₂ O ₃	Al ₂ O ₃	ZnO	NaO	BaO	
Dielectric	60	15	19	6				TiO ₂ +ZnO ₂ +Al ₂ O ₃
layer								

Glass powder of the dielectric layer having the in table 5 has a softening composition shown 450°C. of order temperature In to prepare dielectric layer in a shape of a green tape, poly vinyl buryral and B98 manufactured by Monsanto co., Ltd. were employed as a binder, mixture including MEK, ethyl alcohol, and n-butyl alcohol at a weight ratio of 3:1:1 employed as a solvent, dibutyl phthalate was was employed as a plasticizer, and SN-9228, manufactured by Sanocof co., Ltd., was employed as a dispersing agent. Herein, a binder of 6 wt%, a solvent of 30 wt%, a

plasticizer of 1 wt%, and a dispersing agnet of 8 wt% were added in the powder mixture of 100 wt% for the dielectric layer, in which glass powder and filler are mixed.

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In forming the dielectric layer, slurry including the above-mentioned additives and having a viscosity of 8000 ± 500 cps was prepared in a form of a green tape with a thickness of 37 μm , and was then attached to upper surfaces of the electrodes and the glass substrate through laminating, by a roller at a temperature of 95°C and a pressure of 0.25Mpa.

Thereafter, the attached green tape was baked at a maximum temperature of 530°C for 15 minutes. Then, the completed dielectric layer had a dielectric constant of 18.0, a reflectance of 73%, an etching rate of $0.3\mu\text{m}/\text{min}$ with respect to inorganic acid.

Thereafter, barrier walls equal to those according to experiment 1 were attached to the upper surface of the dielectric layer through laminating by a roller at a temperature of 105°C and a pressure of 0.3Mpa, and were then baked together with the dielectric layer at a maximum temperature of 530°C for 15 minutes. In this the dielectric layer was formed to case, thickness of 25 μm , and each of the formed barrier walls were formed to have a thickness of 150 μm , in which the first, second, and third layers of each barrier wall have 56 μm , 50 μm , 44 μm , respectively. uppermost and widths of the the portions of each barrier wall, and the pitch between

barrier walls were arranged to be the same as those in experiment 1.

Thereafter, phosphorous layers were formed in the same manner as that in experiment 1, excepting that each phosphorous layer was formed to have a thickness of 14µm.

Table 6 shows properties of PDPs employing a rear plate according to experiment 2 and a conventional rear plate, respectively.

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Table 6
Measured properties of PDPs employing a rear plate according to experiment 2 and a conventional rear

plate:			
	Class	PDP	PDP
		employing	employing
		conventional	rear plate
		rear plate	of
		·	experiment 2
	Pitch	250 <i>µ</i> m	250μm
Number	of firings of rear plate	4 times	3 times
	Discharge space	100%	106%
Optical	White Peak brightness	100%	130%
properties	Color temperature(K)	8500	8796
	Contrast	100%	125%
Electrical	Voltage margin	100%	137%
properties	Power consumption	100%	89%
	Module efficiency	100%	121%

	High town /law town orrengens	No	No
reliability	High temp./low temp. erroneous	INO	NO
	discharge		
	vibration/drop_test	Ио	Ио
		progressive	progressive
		defect	defect
Other	noise (dB)	100%	75%
properties			

As apparent from table 6, like the PDP employing a rear plate according to experiment 1 of the present invention, a PDP employing a rear plate according to experiment 2 of the present invention has shown improvement in electric and optical characteristics and reliability, in comparison with a PDP employing a conventional rear plate.

10 Experiment 3

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Electrodes in experiment 3 are the same as the electrodes in experiment 2.

An electrode layer and a barrier wall layer were prepared in a shape of a green tape, respectively, and were then integrated with each other, thereby forming a lamination of electrode layer/barrier wall layer having a form of a green tape.

Thereafter, the lamination of electrode layer/barrier wall layer was laminated on the upper surfaces of the electrodes. Tables 7 and 8 show composition of the dielectric layer and the barrier wall layer, respectively.

Table 7
Composition of the dielectric layer in experiment 3:

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Class	•	Gradie		Filler				
	PbO	SiO ₂	B ₂ O ₃	Al ₂ O ₃	ZnO	NaO	BaO	
Dielectric	53	13	6	12	10	0	2	TiO ₂ +Al ₂ O ₃
layer								·

Glass powder of the dielectric layer having the composition shown in table 7 has softening temperature of 535°C. In order to prepare dielectric layer in a shape of a green tape, PVB and B98 manufactured by Monsanto co., Ltd. were employed as a binder, mixture including toluene, ethanol, and nbutyl alcohol was employed as a solvent, dibutyl phthalate was employed as a plasticizer, and SN-9228, manufactured by Sanoncof co., Ltd., was employed as a dispersing agent. Herein, a binder of 12 wt%, a solvent of 20 wt%, a plasticizer of 1 wt%, and a dispersing agent of 4 wt% were added in the powder mixture of 100 wt% for the dielectric layer, in which glass powder and filler are mixed. The solvent of 20 wt% includes toluene of 4 wt%, ethanol of 1 wt%, and n-butyl alcohol of 1 wt%, mixed therein. As a result, a dielectric layer was formed in a shape of a green tape having a viscosity of 8000±500 cps.

Next, the dielectric layer formed as described above was baked at a maximum temperature of 550°C for 15 minutes. Then, the completed dielectric layer was

observed to have a dielectric constant of 13.2, a reflectance of 69%, an etching rate of $0.12\mu\text{m/min}$ with respect to inorganic acid.

Table 8
Composition of the barrier wall in experiment 3:

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Class			Gradier	nts of	glass p	owder (w	t%)		Filler .
, i	PbO	ZnO	SiO ₂	B ₂ O ₃	Al ₂ O ₃ +	Li ₂ O+	BaO	CaO+	
					ZnO ₂	Na ₂ O+		Mg+	
						K ₂ O		SrO	
1 st	0	19	6	37	o	38	0	0	TiO ₂ +ZnO ₂
layer									+Al ₂ O ₃
2 nd	0	22	21	30	5	21	1	0	ZrO ₂ +
layer									Al ₂ O ₃

In order to prepare the dielectric layer having a composition as shown in Table 8 in a shape of a green tape, PVB manufactured by Monsanto co., Ltd. was employed as a binder, mixture including toluene and isopropyl alcohol was employed as a solvent, dibutyl phthalate manufactured by Yakuri company was employed as a plasticizer, and KD-1 manufactured by ICI Chemical was employed as a dispersing agent.

Herein, a binder of 10 wt%, a solvent of 20 wt%, a plasticizer of 20 wt%, and a dispersing agent of 1 wt% were added in the powder mixture of 100 wt% for the barrier walls, in which glass powder and filler are mixed. The solvent of 20 wt% includes toluene of 8 wt% and isopropyl alcohol of 2 wt%, mixed therein. As a

result, the barrier walls were formed in a shape of green tapes having a viscosity of 9500±500 cps. In this case, each of the barrier walls consists of two overlapping layers.

Table 9 shows properties of the barrier wall according to experiment 3.

Table 9
Properties of the barrier wall according to experiment
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cla	ass	Soften-	Thermal	Average	Dielec-	Reflec	Etching
		ing	expansive	particle	tric	-tion	rate
		tempera-	coeffic.	dia.	const.	ratio	(µm/Min
		ture	(x 10 ⁻⁷ /℃)	(<i>μ</i> an)		(%))
		(3)					
Parti	1 st	475	79	3.5	20	65	42.0
-tion	layer						
wall	2 nd	481	93	9.1	17	67	30.9
	layer						

Hereinafter, a method of integrating the dielectric layer and the barrier wall layer with each other will be briefly described.

15 After the dielectric layer was cast, the first and second layers of the barrier wall layer sequentially cast on the upper surface dielectric layer, and then each layer was preliminary dried at $75\,^{\circ}\mathrm{C}$, so that a lamination of dielectric 20 layer/barrier wall layer having a shape of

integrated green tape was formed. Then, the lamination of dielectric layer/barrier wall layer was completely dried at 145° C, and was then attached to the upper surfaces of the electrodes and the glass substrate by a roller at a pressure of 0.3 MPa and temperature of 105℃. lamination Thereafter, the of dielectric layer/barrier wall layer was baked for fifteen minutes maximum temperature of 550℃, so that dielectric layer was formed to have a thickness of 23 μm the barrier wall layer was formed to thickness of 130 μ m. In the barrier wall layer, the first layer was formed to have a thickness of 103 μ m and the second layer was formed to have a thickness of 27 μ m.

Thereafter, barrier walls were formed by working the partition layer in the same manner as in experiment 1, so that each barrier wall had an uppermost portion with a width of 60 μ m and a lowermost portion with a width of 130 μ m.

Further, phosphorous layers were formed in the same manner as in experiment 1. Each phosphorous layer was formed to have a thickness of 13μ m.

Table 10 shows properties of PDPs employing a rear plate according to experiment 3 and a conventional rear plate, respectively.

Table 10

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Measured properties of PDPs employing a rear plate according to experiment 3 and a conventional rear

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plate:			<u> </u>	
	Class	PDP	PDP	
		employing	employing	
		conventional	rear plate	
	•	rear plate	of	
			experiment 3	
	Pitch	220 <i>µ</i> m	220 <i>µ</i> m 220 <i>µ</i> m	
Number	of firings of rear plate	4 times 3 times		
Discharge space		100%	105%	
Optical	White Peak brightness	100%	125%	
properties	Color temperature(K)	8500	8647	
	Contrast	100%	120%	
Electrical	Voltage margin	100%	125%	
properties	Power consumption	100%	92%	
	Module efficiency	100%	115%	
reliability	High temp./low temp. erroneous	No	No	
	discharge			
	vibration/drop test	No	No	
		progressive	progressive	
		defect	defect	
Other	noise (dB)	100%	75%	
properties				

As apparent from table 10, like the PDPs employing rear plates according to experiments 1 and 2, a PDP employing a rear plate according to experiment 3 of the present invention has shown improvement in electric and optical characteristics and reliability, in comparison with a PDP employing a conventional rear plate.

Further, as noted from experiments 1, 2, and 3 of the present invention, in a PDP employing a rear plate according to the present invention, each barrier wall has a narrower lower portion than that in a PDP employing the conventional rear plate, so that the discharge space increases 5% and the number of firing times can be reduced.

Industrial Applicability

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As can be seen from the foregoing, in a rear plate 10 of a plasma display panel according to the present invention, a dielectric layer or a barrier wall layer is formed by forming slurry in a tape of a green tape and then attaching the green tape to upper surfaces of 15 electrodes and a glass substrate. Therefore, a PDP employing a rear plate according to the present invention has superior electric and optical characteristics.

While this invention has been described in connection with what is presently considered to be the most practical and preferred embodiment, it is to be understood that the invention is not limited to the disclosed embodiment and the drawings, but, on the contrary, it is intended to cover various modifications and variations within the spirit and scope of the appended claims.